

Title (en)
METHOD FOR FORMING ISOLATION STRUCTURE

Title (de)
VERFAHREN ZUR HERSTELLUNG EINER ISOLATIONSSTRUKTUR

Title (fr)
PROCÉDÉ DE FABRICATION D'UNE STRUCTURE D'ISOLATION

Publication
EP 2637203 B1 20200325 (EN)

Application
EP 11838049 A 20111102

Priority
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• JP 2011075265 W 20111102

Abstract (en)
[origin: EP2637203A1] To provide a method for forming an isolation structure having a low shrinkage percentage and a low tensile stress. [Means for solving] A first polysilazane composition containing a porogen is cast on the surface of a substrate to form a coat, and then the coat is fired to form a porous siliceous film having a refractive index of 1.3 or less. Thereafter, the surface of the porous siliceous film is soaked with a second polysilazane composition, and then fired to form an isolation structure of a siliceous film having a refractive index of 1.4 or more.

IPC 8 full level
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CPC (source: EP KR US)
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